## 物理的気相輸送法を用いた 4H-SiC 単結晶成長における基底面転位の 3 次元解析 Three-dimensional modeling of basal plane dislocations in 4H-SiC single crystal grown by the physical vapor transport method <sup>○</sup>高 冰,中野 智,柿本 浩一 九州大学応用力学研究所 <sup>°</sup>B. Gao, S. Nakano, K. Kakimoto Research Institute for Applied Mechanics, Kyushu University, Japan

Email: gaobing@riam.kyushu-u.ac.jp

## **Introduction**

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In bulk SiC PVT growth, significant progress has been achieved in reducing the most damaging defects: micropipes. In 2007, researchers at Cree Inc. reduced the micropipe density (MPD) by 90% in 150-mm substrates. As the density of micropipes in SiC crystals has been suppressed to a technologically tolerable level, quality improvement focus has shifted to less severely damaging defects such as dislocations. There are several types of dislocations, including basal plane dislocations (BPDs), which are deformation-induced dislocations, and grown-in dislocations (TED and TSD). In this paper, we develop a 3D model that can correctly describe the rate-dependent plastic deformation process of SiC crystal, and can effectively connect the generation of BPDs to the practical operational conditions.

## **Proposed solutions**

To correctly track plastic deformation during high-temperature PVT growth, we improved the model proposed by Gao *et al.*[1] by first resolving thermal stress in the primary slip direction in 4H-SiC, and then substituting the resolved shear stress into the three-dimensional (3D) Alexander–Haasen model to obtain the BPDs.

## **Results**

Fig. 1 shows the BPD distribution at growth times of 35, 42.5, 50, and 57.5 h. The crystal grows from the top to the bottom. The surface of the crystal bottom is slightly convex. The order of the BPD density at the crystal bottom is  $10^4 \text{ cm}^{-2}$ , and it shows six-fold symmetry on the basal plane, which is consistent with the experimental data [2]. It shows that the large BPDs were mainly generated between



Fig. 1. 3D view of the BPD distribution at different growth times: (a) 35 h, (b) 42.5 h,(c) 50 h, and (d) 57.5 h.

42.5 h (Fig. 1(b)) and 50 h (Fig. 1(c)). Therefore, it is growth process mainly causing large BPD generation. **References** 

[1] B. Gao, K. Kakimoto, J. Cryst. Growth 2014, 386, 215-219.

[2] S. A. Sakwe et al., Silicon Carbide, Edited by P. Friedrichs et al., pp1-31.